

WEST Search History

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DATE: Sunday, February 15, 2004

<u>Hide?</u>	<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>
<i>DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L15	l13 and l16	20
<input type="checkbox"/>	L14	L12 same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) ((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer)) and (delay\$3 or (pos\$3-pon\$3) or (pos\$3 pon\$3))	0
<input type="checkbox"/>	L13	spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer)) and (delay\$3 or (pos\$3-pon\$3) or (pos\$3 pon\$3))	912
<input type="checkbox"/>	L12	(pos\$3-pon\$3) or (pos\$3 pon\$3) ((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer)) and (delay\$3 or post-pon\$3)	82
<input type="checkbox"/>	L11	((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer)) and (delay\$3 or post-pon\$3)	912
<input type="checkbox"/>	L10	((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer)) and delay\$3	912
<input type="checkbox"/>	L9	L7 and ((swel\$5 or swol\$5) same (planar\$7 or polish\$3 or CMP))	5
<input type="checkbox"/>	L8	L7 and ((swel\$5 or swol\$5) same planar\$7 or polish\$3 or CMP)	275
<input type="checkbox"/>	L7	216/38.ccls.	369
<input type="checkbox"/>	L6	134/1.3,2,3,26,28,34,41;438/906.ccls. (semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) with delay\$3)	8724
<input type="checkbox"/>	L5	(semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) with delay\$3)	38
<input type="checkbox"/>	L4	(semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) with action with delay\$3)	0
<input type="checkbox"/>	L3	((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) same action) and delay\$3)	44
<i>DB=USPT; PLUR=YES; OP=ADJ</i>			
<input type="checkbox"/>	L2	((semiconductor or substrate or wafer) same (clean\$3 or wash\$3 or rins\$3 or spray\$3 or etch\$3) same (ultrasonic\$5 or megasonic\$5 or sonic\$5 or transducer) same action) and kornakov	4
<input type="checkbox"/>	L1	6666987.pn.	1

END OF SEARCH HISTORY